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| OI OCT 14 2005 (37 CFR §1.98(b)) <small>PATENT & TRADEMARK OFFICE</small> | Substitute Form PTO-1449 (Modified) | | U.S. Department of Commerce Patent and Trademark Office | Attorney's Docket No. 10559-887001 | Application No. 10/649,354 |
| | Information Disclosure Statement by Applicant (Use several sheets if necessary) | | Applicant Florence Eschbach et al. | | |
| | | | Filing Date August 26, 2003 | Group Art Unit 1773 | |
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| U.S. Patent Documents | | | | | | | |
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| Examiner Initial | Desig. ID | Document Number | Publication Date | Patentee | Class | Subclass | Filing Date If Appropriate |
| | AA | | | | | | |
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| Foreign Patent Documents or Published Foreign Patent Applications | | | | | | | Translation | |
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| Examiner Initial | Desig. ID | Document Number | Publication Date | Country or Patent Office | Class | Subclass | Yes | No |
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| Other Documents (include Author, Title, Date, and Place of Publication) | | |
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| Examiner Initial | Desig. ID | Document |
| M | AO | Chen, et al., "Pellicle-Induced Reticle Distortion: An Experimental Investigation", <i>Proc. of SPIE - The Int'l Soc. for Optical Engineering</i> , Vol. 3546, pp. 167-172 (1998). |
| | AP | Cotte, et al., "Effects of Soft Pellicle Frame Curvature and Mounting Process on Pellicle-Induced Distortions in Advanced Photomasks", <i>Proc. of SPIE - The Int'l Soc. for Optical Engineering</i> , Vol. 5040, pp. 1044-1054 (2003). |
| | AQ | Cotte, et al., "Experimental and Numerical Studies of the Effects of Materials and Attachment Conditions on Pellicle-Induced Distortions in Advanced Photomasks", <i>Proc. of SPIE - The Int'l Soc. for Optical Engineering</i> , Vol. 4754, pp. 579-588 (2002). |
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| Examiner Signature | Date Considered |
| | 12/6/05 |
| EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. | |